

Abstract (FIG. 1)

"SUBSTRATE PROCESSING APPARATUS"

5 A first processing unit group for performing
solution processing and a second processing unit group
including heat and cooling processing units each having
a heat processing unit and a cooling processing unit
are arranged adjacent to each other such that the
10 cooling processing unit is located on the first
processing unit group side. This makes it possible to
conduct temperature control precisely in a solution
processing unit for performing solution processing for
a substrate at about room temperature.



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